



Integrated Device Technology, Inc.
2975 Stender Way, Santa Clara, CA - 95054

PRODUCT/PROCESS CHANGE NOTICE (PCN)

ATTACHMENT - PCN #: L0105-03

PCN Type: Die revision

Data Sheet Change Yes.

Following data sheet limits have been revised due to the enhanced device performance:

Test Parameter	Old Limit	New Limit
t_{PZLZH}	9 ns	7 ns
t_{PLZHZ}	8 ns	6.5 ns
f_{OE}	1 MHz	20 MHz

Detail of Change

The die has been revised from "XQ" and "QC" stepping to "Z" stepping to enhance the device performance.
Selective data sheet limits have been revised due to the enhanced device performance.

Die Revision Details

	<u>Current Die Rev - XQ</u>	<u>Current Die Rev - QC</u>	<u>New Die Rev - Z</u>
Wafer Fab Technology	0.8 μ	0.8 μ	0.8 μ
Poly Gate	0.8 μ	0.8 μ	0.8 μ
Minimum Gate Oxide Thickness	150 Å	150 Å	150 Å
Wafer Size	6 "	6 "	6 "
Fab Facility	Fab 5 (PSA, Australia)	Fab 2 (Salinas, USA)	Fab 2 (Salinas, USA)
Date Code Prefix	XQ	QC	Z

Conversion schedule (Estimated)

	Sample Availability	Production Shipments
QS3VH245	Available	08/24/01
QS32XVH245	Available	08/24/01
QS34XVH245	Available	08/24/01



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Qualification Plan QLG-01-01

Test Vehicle: QS3VH862

Qualification Test Plan and Results:

Test Description	SS/Acc #	Test Results
Dynamic High Temp Operating Life Test Mil-Std-883, Method-1005	116/0	116/0
ESD - HBM Mil-Std-883, Method-3015	3/0	3500 Volts
ESD-CDM JESD22-C101	3/0	1000 Volts
ESD-MM EIAJ-IC-121	3/0	400 Volts
Latch-up EIA/JESD78	10/0	10/0

Characterization Data:

Characterization data is available upon request.